

METHOD FOR FABRICATING THIN FILM TRANSISTORS

ABSTRACT

[0036] A method is disclosed for forming a thin film field effect transistor. A photoresist layer is formed on top of the preliminary substrate. A portion of the photoresist layer is selectively removed in a single exposure process to form a photoresist pattern having a two-portion structure with a first portion having a first width and a second portion underneath the first portion with a second width. Such a photoresist pattern helps to reduce the number of mask processes used for forming the thin film field effect transistor.